- 1 -

Docket: 0756-7218

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re DIVISIONAL application of)
Shunpei YAMAZAKI et al.)
Based on Serial No. 10/214,691) Group Art Unit: 2826
Filed: August 9, 2002) Examiner: Abraham
For: SEMICONDUCTOR DEVICE AND)
METHOD OF FABRICATING SAME

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56 and 37 C.F.R. 1.97-1.99, Applicant submits herewith a Form PTO-1449 listing references known to Applicant and requests that these references be made of record in the above identified application. Copies of the references listed are submitted herewith in accordance with 37 C.F.R. 1.98(a).

The references listed on the attached Form PTO-1449 were cited in parent application Serial No. 10/214,691 and predecessor Application Serial No. 08/785,486 and copies of the references can be found in those applications.

Respectfully submitted,

Eric J. Robinson Reg. No. 38,285

Robinson Intellectual Property Law Office PMB 955

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Signature

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Substitute	for form 1449A/PTO			Complete	if Known		
INFO	DMATION	rec	OSUDE	Application Number	Based on 10/214,691		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Filing Date	August 9, 2002				
		First Named Inventor	Shunpei YAMAZAKI, et al.				
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				Examiner Name	Fetsum Abraham Benjamin	T	Liv
Sheet	1	of	12	Attorney Docket Number	0756-7218		

			U.S. PATENT DOCUMENT	rs	
Examiner Cite Initials* No.		U.S. Patent Document	Name of Patentee or Applicant of Cited	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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/BTL/		Japan J. Appl. Phys. 8 (1969) 10: Temperature of Amorphous Gerr		tals on the Crystallization	
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Examiner	T	/Benjamin Tzu-Hung Liu/	Date	04/28/2008	

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Considered

¹ Unique citation designation number, ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST3), ³ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ³ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST1.6 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.

PTO/SB/08A (08-00)
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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449A/PTO Application Number Based on 10/214.691 INFORMATION DISCLOSURE August 9, 2002 Filing Date STATEMENT BY APPLICANT Shunpei YAMAZAKI, et al. First Named Inventor (use as many sheets as necessary) 2826 Group Art Unit Fetsum Abraham Examiner Name Benjamin T Liu Sheet 12 Attorney Docket Number 0756-7218

				U.S. PATENT DOCUMENT	rs	
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Examiner Initials	Cite No.1		Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazzine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and dro country where published.						
/BTL/		IBN	Technical I	Disclosure	Bulletin, Vol. 11, N	lo.7, A.R. B	aker, Jr.		
Examiner Signature	1	/B	enjamin Tzu-H	lung Liu/		Date Considered	04/	28/2008	

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SIA				First Named Inventor	Shunpei YAMAZAKI, et al.		
	(use as many sheets	as necesso	ary)	Group Art Unit	2826		
				Examiner Name	Fetsum Abraham Benjamir		
Sheet	Sheet 3 of 12			Attorney Docket Number	0756-7218		

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	STATEMENT BY APPLICANT			Filing Date	August 9, 2002		
SIA				First Named Inventor	Shunpei YAMAZAKI, et al.	ı	
(use as many sheets as necessary)		Group Art Unit	2826	ı			
				Examiner Name	Fetsum Abraham Benjamin	T	Liu
Sheet	4	of	12	Attorney Docket Number	0756-7218	ı	

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	Examiner Signature	/Benjamin Tzu-Hung Liu/	Date Considered	04/28/2008
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Substitut	e for form 1449A/PTO			0	Complete if Known		
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				Filing Date	August 9, 2002		
SIA			First Named Inventor	Shunpei YAMAZAKI, et al.	7		
	(use as many sheets as necessary) Sheet 5 of 12			Group Art Unit	2826		
				Examiner Name	Fetsum Abraham Benjamin	T	Lit
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Examiner Signature	/Benjamin Tzu-Hung Liu/	Date Considered	04/28/2008

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Sheet	6	of	12	Attorney Docket Number	0756-7218		

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Signature		Considered	04/20/2000

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				(עיני	Group Art Unit	2826	1	
					Examiner Name	Petsum Abraham Benjamin	T	Liı
	Sheet	7	of	12	Attorney Docket Number	0756-7218	l	

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xaminer nitials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium castleg, etc.), date, page(s), volume-issue number(s), publisher, cinya under country where published.	T²				
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				Examiner Name	Fotoum Abraham Benjamin		
Sheet	8	of	12	Attorney Docket Number	0756-7218		

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